

Search Report

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To: KIET NGUYEN Location: JEF-4D49

Art Unit: 2881

Friday, August 10, 2007

Case Serial Number: 09836743

From: DIANE JACKSON

Location: EIC2800 JEF-4B68 / JEF-4B68 Phone: (571)272-3260

diane.jackson@uspto.gov

Search Notes:

Attached are litigation search results in Lexis Nexis, and CourtLink and Questel-Orbit.

No Litigation was found for Serial Number 09/836743.

If you have any questions, please feel free to contact me.

Thanks,

Diane



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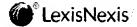
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Patent Search 6020592 8/10/2007

No cases found.

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Source: Combined Source Set 10 i - Utility, Design and Plant Patents
Terms: patno=6020592 (Edit Search | Suggest Terms for My Search)

128370 (09) 6020592 February 1, 2000

UNITED STATES PATENT AND TRADEMARK OFFICE GRANTED PATENT

6020592

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Order Patent File History / Wrapper from REEDFAX® Link to Claims Section

February 1, 2000

Dose monitor for plasma doping system

REISSUE: April 17, 2001 - Reissue Application filed Ex. Gp.: 2878; Re. S.N. 09/836,743 (O.G. June 19, 2001)

INVENTOR: Liebert, Reuel B. - Peabody, Massachusetts, United States (US); Pedersen, Bjorn O. - Chelmsford, Massachusetts, United States (US); Goeckner, Matthew - Palo Alto, California, United States (US)

APPL-NO: 128370 (09)

FILED-DATE: August 3, 1998

GRANTED-DATE: February 1, 2000

ASSIGNEE-PRE-ISSUE: August 3, 1998 - ASSIGNMENT OF ASSIGNORS INTEREST (SEE DOCUMENT FOR DETAILS)., VARIAN ASSOCIATES, INC. LEGAL DEPARTMENT M/S E-339 3100 HANSEN WAYPALO ALTO, CALIFORNIA, 94304, Reel and Frame Number: 009368/0590 May 10, 1999 - ASSIGNMENT OF ASSIGNORS INTEREST (SEE DOCUMENT FOR DETAILS)., VARIAN SEMICONDUCTOR EQUIPMENT ASSOCIATES, INC. 35 DORY ROADGLOUCESTER, MASSACHUSETTS, 01930, Reel and Frame Number: 010023/0940

ASSIGNEE-AT-ISSUE: Varian Semiconductor Equipment Associates, Inc., Gloucester, Massachusetts, United States (US), United States company or corporation (02)

LEGAL-REP: Wolf, Greenfield & Sacks, P.C.

PUB-TYPE: February 1, 2000 - Utility Patent having no previously published pre-grant publication (A)

PUB-COUNTRY: United States (US)

US-MAIN-CL: 250#492.21

CL: 250

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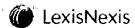
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Patent Search 6300643 8/10/2007

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Source: Combined Source Set 10 i - Utility, Design and Plant Patents
Terms: patno=6300643 (Edit Search | Suggest Terms for My Search)

455550 (09) 6300643 October 9, 2001

UNITED STATES PATENT AND TRADEMARK OFFICE GRANTED PATENT

6300643

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Order Patent File History / Wrapper from REEDFAX® Link to Claims Section

October 9, 2001

Dose monitor for plasma doping system

INVENTOR: Fang, Ziwei - Sunnyvale, California, United States (US); Goeckner, Matthew - Plano, Texas, United States (US)

CERT-CORRECTION: April 29, 2003 - a Certificate of Correction was issued for this patent (O.G. May 20, 2003)

APPL-NO: 455550 (09)

FILED-DATE: December 6, 1999

GRANTED-DATE: October 9, 2001

ASSIGNEE-PRE-ISSUE: February 28, 2000 - ASSIGNMENT OF ASSIGNORS INTEREST (SEE DOCUMENT FOR DETAILS)., VARIAN SEMICONDUCTOR EQUIPMENT ASSOCIATES, INC. 35 DORY ROADGLOUCESTER, MASSACHUSETTS, 01930, Reel and Frame Number: 010583/0565

ASSIGNEE-AT-ISSUE: Varian Semiconductor Equipment Associates, Inc., Gloucester, Massachusetts, United States (US), United States company or corporation (02)

LEGAL-REP: Wolf, Greenfield & Sacks, P.C.

PUB-TYPE: October 9, 2001 - Utility Patent having no previously published pre-grant publication (B1)

PUB-COUNTRY: United States (US)

REL-DATA:

Continuation-in-part of Ser. No. 09/128370, August 3, 1998, GRANTED PATENT 6020592, Utility Patent having no previously published pre-grant publication (A)

US-MAIN-CL: 250#492.21

US-ADDL-CL: 250#397

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Source: Combined Source Set 10 - Utility, Design and Plant Patents
Terms: patno=6528805 (Edit Search | Suggest Terms for My Search)

916998 (09) 6528805 March 4, 2003

UNITED STATES PATENT AND TRADEMARK OFFICE GRANTED PATENT

6528805

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March 4, 2003

Dose monitor for plasma doping system

INVENTOR: Fang, Ziwei - Sunnyvale, California, United States (US); Goeckner, Matthew - Plano, Texas, United States (US)

APPL-NO: 916998 (09)

FILED-DATE: July 27, 2001

GRANTED-DATE: March 4, 2003

ASSIGNEE-AT-ISSUE: Varian Semiconductor Equipment Associates, Inc., Gloucester, Massachusetts, United States (US), United States company or corporation (02)

PUB-TYPE: March 4, 2003 - Utility Patent having a previously published pre-grant publication (B2)

PUB-COUNTRY: United States (US)

REL-DATA:

Division of Ser. No. 09/455550, December 6, 1999, GRANTED PATENT 6300643, Utility Patent having no previously published pre-grant publication (A)

, which is a Continuation-in-part of Ser. No. 09/128370, August 3, 1998, GRANTED PATENT 6020592, Utility Patent having no previously published pre-grant publication (A) Prior Publication 20010042827, November 22, 2001, PENDING

US-MAIN-CL: 250#492.21

US-ADDL-CL: 250#397

CL: 250

SEARCH-FLD: 250#492.1, 250#397, 324#71.3, 324#72

IPC-MAIN-CL: [7] H01J 037#244

Query/Command: prt ful legalall max

1/6 FAMPAT - @QUESTEL-ORBIT - image FAN 20042792667016 PN 🔁 WO200141183 A1 20010607 [WO200141183] STG: Publ. Of int. Appl. With int. Search rep **AP**: 2000WO-US32576 20001129 TW483021 B 20020411 [TW-483021] STG: Patent **AP**: 2000TW-0125958 20001206 WO200141183 A8 20020523 [WO200141183] STG: Modified first page WO200141183 A9 20020620 [WO200141183] STG: Complete corrected document EP1236221 A1 20020904 [EP1236221] STG: Public. Of applic. With search report **AP**: 2000EP-0982300 20001129 JP2003515945 T 20030507 [JP2003515945] STG: Unexam. Pat. Appl. On foreign appl. AP: 2001JP-0542358 20001129 TI DOSE MONITOR FOR PLASMA DOPING SYSTEM PA VARIAN SEMICONDUCTOR EQUIPMENT Varian Semiconductor Equipment Associates Inc.; 35 Dory Road; Gloucester, MA 01930 PA₀ (US) FANG ZIWEI; GOECKNER MATTHEW IN PR 1999US-0455550 19991206; 2000WO-US32576 20001129 IC C23C-014/48 H01J-037/244 H01J-037/32 H01L-021/265 ICAA -H01J-037/32 [2006-01 A - I R M EP] **ICCA** H01J-037/32 [2006 C - I R M EP] EC H01J-037/32D1C1 H01J-037/32J (EP1236221) DS AT BE CH CY DE DK ES FI FR GB GR IE IT LI LU MC NL PT SE TR AL LT LV MK RO SI (WO200141183) DS IL JP KR European Patent (AT BE CH CY DE DK ES FI FR GB GR IE IT LU MC NL PT SE TR) (EP1236221) CT Revealed during examination US4751393(A); US5814823(A) See also references of WO 0141183A1 **CT** (WO200141183) Cited in the search report

US5103161(A)(Cat. X);EP860854(A1)(Cat. Y);US5583427(A)(Cat. Y);WO0008670(A2)

(Cat. A,P,D);EP532283(A1)(Cat. A) See also references of EP 1236221A1

AB - (WO200141183)

Plasma doping apparatus includes a plasma doping chamber, a platen mounted in the plasma doping chamber for supporting a workpiece such as a semiconductor wafer, a source of ionizable gas coupled to the chamber, an anode spaced from the platen and a pulse source for applying voltage pulses between the platen and the anode. The voltage pulses produce a plasma having a plasma sheath in the vicinity of the workpiece. The voltage pulses accelerate positive ions across the plasma sheath toward the platen for implantation into the workpiece. The plasma doping apparatus includes at least one Faraday cup positioned adjacent to the platen for collecting a sample of the positive ions accelerated across the plasma sheath. The sample is representative of the dose of positive ions implanted into the workpiece.+DBPH+ The Faraday cup may include a multi-aperture cover for reducing the risk of discharge within the interior chamber of the Faraday cup. The Faraday cup may be configured to produce a lateral electric field within the interior chamber for suppressing escape of electrons, thereby improving measurement accuracy.

OBJ - (WO200141183)

This application is a continuation-in-part of pending application Serial No. 09/128,370 This invention relates to plasma doping systems used for ion implantation of workpieces and, more particularly, to methods and apparatus for measuring the ion dose According a first aspect of the invention, plasma doping apparatus is provided.

ADB - (WO200141183)

Accordingly, there is a need for improved methods and apparatus for measuring ion dose implanted into a workpiece in plasma doping systems.

The annular Faraday cup 80 has the advantage that localized variations in ion current are averaged around the periphery of wafer 20.

The effective range for using the Faraday cup as a dose monitor is therefore limited due to this discharge problem.

This eliminates the discharge problem within the Faraday cup and extends the operational range of the Faraday cup to higher pressures and lower voltages.

This effect, known as the space charge effect, must be taken into consideration when the ion density is above 108 ions per cubic centimeter.

ICLM - (WO200141183)

- 19. Plasma doping apparatus comprising:
- a plasma doping chamber;
- a platen mounted in said plasma doping chamber for supporting a workpiece, said platen and the workpiece constituting a cathode;
- a source of ionizable gas coupled to said chamber, said ionizable gas containing a desired dopant for implantation into the workpiece;
- an anode spaced from said platen;
- a pulse source for applying voltage pulses between said platen and said anode for producing a plasma having a plasma sheath in the vicinity of said workpiece, said plasma containing positive ions of said ionizable gas, said voltage pulses accelerating positive ions across the plasma sheath toward said platen for implantation into the workpiece;
- a Faraday cup positioned adjacent to said platen for collecting a sample of said positive ions accelerated across said plasma sheath, said sample being representative of the number of positive ions implanted into the workpiece, said Faraday cup including means for producing within an interior chamber of said Faraday cup an electric field lateral to the direction of ions entering said Faraday cup.

24. A Faraday cup for sensing an ion beam, comprising:

a sidewall and a bottom wall defining an interior chamber, said interior chamber having an opening; and

a cover disposed over said opening, said cover having a plurality of apertures for allowing ions to enter the interior chamber.

31. A Faraday cup for sensing an ion beam, comprising:

a sidewall and a bottom wall defining an interior chamber, said interior chamber having an opening; and

means for producing within the interior chamber of said Faraday cup an electric field lateral to the direction of ions entering said Faraday cup.

UP - 2003-23

1/3 LGST - ©EPO

PN - TW483021 B 20020411 [TW-483021]

AP - TW89125958 20001206 [2000TW-0125958]

ACT - 20020821 TW/GD4A-A [+]

ISSUE OF PATENT CERTIFICATE FOR GRANTED INVENTION PATENT ISSUE OF PATENT CERTIFICATE FOR GRANTED INVENTION PATENT

20040511 TW/MM4A-A [-]

ANNULMENT OR LAPSE OF PATENT DUE TO NON-PAYMENT OF FEES ANNULMENT OR LAPSE OF PATENT DUE TO NON-PAYMENT OF FEES

UP - 2004-31

2/3 LGST - ©EPO

PN - D WO200141183 A1 20010607 [WO200141183]

WO200141183 A8 20020523 [WO200141183]

WO200141183 A9 20020620 [WO200141183]

AP - WOUS0032576 20001129 [2000WO-US32576]

At - WOOSOO32370 20001129 [2000WO-0832370]

ACT - 20010607 WO/AK [+] DESIGNATED STATES

IL JP KR

20010607 WO/AL [+]

DESIGNATED COUNTRIES FOR REGIONAL PATENTS

AT BE CH CY DE DK ES FI FR GB GR IE IT LU MC NL PT SE TR

`20010801 WO/121

EP: THE EPO HAS BEEN INFORMED BY WIPO THAT EP WAS DESIGNATED IN THIS APPLICATION

20011018 WO/DFPE

REQUEST FOR PRELIMINARY EXAMINATION FILED PRIOR TO EXPIRATION OF 19TH MONTH FROM PRIORITY DATE

20020523 WO/CFP

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20020523 WO/AK [+]
DESIGNATED STATES
CN IL JP KR

20020523 WO/AL [+]
DESIGNATED COUNTRIES FOR REGIONAL PATENTS
AT BE CH CY DE DK ES FI FR GB GR IE IT LU MC NL PT SE TR

20020531 WO/ENP ENTRY INTO THE NATIONAL PHASE IN: JP 2001 542358A [2001JP-0542358]

20020605 WO/WWE [+] WIPO INFORMATION: ENTRY INTO NATIONAL PHASE < 1020027007166 >

20020620 WO/AK [+] DESIGNATED STATES CN IL JP KR

20020620 WO/AL [+]
DESIGNATED COUNTRIES FOR REGIONAL PATENTS
AT BE CH CY DE DK ES FI FR GB GR IE IT LU MC NL PT SE TR

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20020713 WO/WWP [+] WIPO INORMATION: PUBLISHED IN NATIONAL OFFICE < 1020027007166 >

UP - 2006-42

3/3 LGST - ©EPO

PN

- EP1236221 A1 20020904 [EP1236221]

AP - EP00982300 20001129 [2000EP-0982300]

ACT - 20020904 EP/AX-A [+]

EXTENSION OF THE EUROPEAN PATENT TO ERSTRECKUNG DES EUROPAEISCHEN PATENTS AUF

AL;LT;LV;MK;RO;SI

20020904 EP/AK-A [+]
DESIGNATED CONTRACTING STATES:
BENANNTE VERTRAGSSTAATEN

AT BE CH CY DE DK ES FI FR GB GR IE IT LI LU MC NL PT SE TR

20020904 EP/17P-A [+]

REQUEST FOR EXAMINATION FILED PRUEFUNGSANTRAG GESTELLT EFFECTIVE DATE: 20020524

20021030 EP/RIN1-A INVENTOR (CORRECTION) ERFINDER (KORR.) FANG, ZIWEI

20021030 EP/RIN1-A INVENTOR (CORRECTION) ERFINDER (KORR.) GOECKNER, MATTHEW

20040526 EP/RBV-A [+]
DESIGNATED CONTRACTING STATES (CORRECTION):
BENANNTE VERTRAGSSTAATEN (KORR.)
DE FR GB IT

20040908 EP/17Q-A [+] FIRST EXAMINATION REPORT ERSTER PRUEFUNGSBESCHEID EFFECTIVE DATE: 20040723

20070103 EP/17Q-A [+] FIRST EXAMINATION REPORT ERSTER PRUEFUNGSBESCHEID EFFECTIVE DATE: 20040723

UP - 2007-01

Search statement :

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Extended Family Search Results

US6020592/PN Results: 12

PATENT FAMILY

#	Patent No.	Kind	Date	Applic.No.	Date
<u>1)</u>	EP1103063	A2	20010530	1999EP-0938731	19990713
<u>2)</u>	EP1236221	A1	20020904	2000EP-0982300	20001129
<u>3)</u>	JP2002522899	Т	20020723	2000JP-0564222	19990713
4)	JP2003515945	T	20030507	2001JP-0542358	20001129
<u>5</u>)	TW-439084	В	20010607	1999TW-0112659	19990727
6)	TW-483021	В	20020411	2000TW-0125958	20001206
<u>7)</u>	US6020592	Α	20000201	1998US-0128370	19980803
8)	US6300643	B1	20011009	1999US-0455550	19991206
9)	US20020030167	A1	20020314	2001US-0836882	20010417
<u>10)</u>	US20010042827	A1	20011122	2001US-0916998	20010727
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<u>11)</u>	WO200008670	A2	20000217	1999WO-US15790	19990713
	WO200008670	A3	20000608	•	·
	WO200008670	A9	20000727	*	
12)	WO200141183	A 1	20010607	2000WO-US32576	20001129
	WO200141183	A8	20020523		
	WO200141183	A9	20020620		
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	Priority:				
	1998US-0128370	•	19980803		
	1999US-0455550		19991206		
	1999WO-US15790		19990713		
	2000WO-US32576	•	20001129	•	• • •
	2001US-0836882		20010417	•	
	2001UŚ-0916998		20010727	•	
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1/12 PLUSPAT - ©QUESTEL-ORBIT

PN - EP1103063 A2 20010530 [EP1103063]

STG - (A2) Pub. Of applic. Without search report

TI - (A2) DOSE MONITOR FOR PLASMA-IMMERSION ION IMPLANTATION DOPING SYSTEM

OTI - (A2) DOSISMONITOR FÜR EINE PLASMAIMMERSIONSIONENDOTIERUNGSVORRICHTUNG
(A2) CONTROLE DES DOSES POUR SYSTEME DE DOPAGE A IMPLANTATION
D'IONS ET IMMERSION DANS DU PLASMA

PA - (A2) VARIAN SEMICONDUCTOR EQUIPMENT (US)

IN - (A2) LIEBERT REUEL B (US); GOECKNER MATTHEW (US); PEDERSEN BJORN O

(US)

IC - (A2) C23C-014/48 H01J-037/32

LA - ENGLISH (ENG)

AP - EP99938731 19990713 [1999EP-0938731]

PR - WOUS9915790 19990713 [1999WO-US15790]

US12837098 19980803 [1998US-0128370]

ICAA - H01J-037/32 [2006-01 A - I R M EP]

ICCA - H01J-037/32 [2006 C - I R M EP]

DS - AT BE CH CY DE DK ES FI FR GB GR IE IT LI LU MC NL PT SE

UP - 2001-22

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PN - EP1103063 A2 20010530 [EP1103063]

AP - EP99938731 19990713 [1999EP-0938731]

ACT - 20010530 EP/AK-A [+]

DESIGNATED CONTRACTING STATES:

BENANNTE VERTRAGSSTAATEN

AT BE CH CY DE DK ES FI FR GB GR IE IT LI LU MC NL PT SE

20010530 EP/17P-A [+]

REQUEST FOR EXAMINATION FILED

PRUEFUNGSANTRAG GESTELLT

EFFECTIVE DATE: 20010129

20040526 EP/RBV-A [+]

DESIGNATED CONTRACTING STATES (CORRECTION):

BENANNTE VERTRAGSSTAATEN (KORR.)

DE FR GB IE IT

UP - 2004-22

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PN - EP1236221 A1 20020904 [EP1236221]

STG - (A1) Public. Of applic. With search report

TI - (A1) DOSE MONITOR FOR PLASMA DOPING SYSTEM

OTI - (A1) DOSISMONITOR FÜR EIN PLASMA-DOTIERUNGSGERÄT

(A1) CONTROLE DES DOSES POUR SYSTEME DE DOPAGE AU PLASMA

PA - (A1) VARIAN SEMICONDUCTOR EQUIPMENT (US)

PAO - Varian Semiconductor Equipment Associates Inc.; 35 Dory Road; Gloucester, MA 01930

(US)

IN - (A1) FANG ZIWEI (US); GOECKNER MATTHEW (US)

IC - (A1) H01J-037/244 H01J-037/32

LA - ENGLISH (ENG)

AP - EP00982300 20001129 [2000EP-0982300]

PR - WOUS0032576 20001129 [2000WO-US32576]

US45555099 19991206 [1999US-0455550]

ICAA - H01J-037/32 [2006-01 A - I R M EP]

ICCA - H01J-037/32 [2006 C - I R M EP]

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UP - 2002-36

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PN - EP1236221 A1 20020904 [EP1236221]

AP - EP00982300 20001129 [2000EP-0982300]

ACT - 20020904 EP/AX-A [+]

EXTENSION OF THE EUROPEAN PATENT TO

ERSTRECKUNG DES EUROPAEISCHEN PATENTS AUF

AL;LT;LV;MK;RO;SI

20020904 EP/AK-A [+]

DESIGNATED CONTRACTING STATES:

BENANNTE VERTRAGSSTAATEN

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20020904 EP/17P-A [+]

REQUEST FOR EXAMINATION FILED

PRUEFUNGSANTRAG GESTELLT

EFFECTIVE DATE: 20020524

20021030 EP/RIN1-A

INVENTOR (CORRECTION)

ERFINDER (KORR.)

FANG, ZIWEI

20021030 EP/RIN1-A

INVENTOR (CORRECTION)

ERFINDER (KORR.)

GOECKNER, MATTHEW

20040526 EP/RBV-A [+]

DESIGNATED CONTRACTING STATES (CORRECTION):

BENANNTE VERTRAGSSTAATEN (KORR.)

DE FR GB IT

20040908 EP/17Q-A [+]

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ERSTER PRUEFUNGSBESCHEID

EFFECTIVE DATE: 20040723

20070103 EP/17Q-A [+]

FIRST EXAMINATION REPORT ERSTER PRUEFUNGSBESCHEID EFFECTIVE DATE: 20040723

UP - 2007-01

(A)

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PN - JP2002522899 T 20020723 [JP2002522899]

STG - (T) Unexam. Pat. Appl. On foreign appl.

IC - (T) C23C-014/48 H01J-037/32 H01L-021/265 AP - JP2000564222T 19990713 [2000JP-0564222]

PR - US12837098 19980803 [1998US-0128370]

WOUS9915790 19990713 [1999WO-US15790]

ICAA - H01J-037/32 [2006-01 A - I R M EP]

ICCA - H01J-037/32 [2006 C - I R M EP]

UP - 2002-35

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4/12 PLUSPAT - ©QUESTEL-ORBIT

PN - JP2003515945 T 20030507 [JP2003515945]

STG - (T) Unexam. Pat. Appl. On foreign appl.

IC - (T) C23C-014/48 H01J-037/32 H01L-021/265

AP - JP2001542358T 20001129 [2001JP-0542358]

PR - US45555099 19991206 [1999US-0455550]

WOUS0032576 20001129 [2000WO-US32576]

ICAA - (kH01J-037/32 [2006-01 A - I R M EP]

ICCA - H01J-037/32 [2006 C - I R M EP]

UP - 2003-23

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5/12 PLUSPAT - ©QUESTEL-ORBIT

PN - TW439084 B 20010607 [TW-439084]

STG - (B) Patent

TI - (B) Dose monitor for plasma doping system

PA - (B): VARIAN SEMICONDUCTOR EQUIPMENT (US)

IN - (B) LIEBERT REUEL B (US); GOECKNER MATTHEW (US); PEDERSEN BJORN O

(US)

IC - (B) H01J-037/00

AP - TW88112659 19990727 [1999TW-0112659]

PR - US12837098 19980803 [1998US-0128370]

ICAA - H01J-037/32 [2006-01 A - I R M EP]

ICCA - H01J-037/32 [2006 C - I R M EP]

UP - 2001-47

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PN - TW439084 B 20010607 [TW-439084]

AP - TW88112659 19990727 [1999TW-0112659]

ACT - 20011027 TW/GD4A-A [+]

ISSUE OF PATENT CERTIFICATE FOR GRANTED INVENTION PATENT ISSUE OF PATENT CERTIFICATE FOR GRANTED INVENTION PATENT

UP - 2004-28

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6/12 PLUSPAT - @QUESTEL-ORBIT

PN - TW483021 B 20020411 [TW-483021]

STG - (B) Patent

TI - (B) Dose monitor for plasma doping system.

PA - (B) VARIAN SEMICONDUCTOR EQUIPMENT (US)

IN - (B) FANG ZIWEI (AU); GOECKNER MATTHEW (US)

IC - (B) H01J-037/244

AP - TW89125958 20001206 [2000TW-0125958]

PR - US45555099 19991206 [1999US-0455550]

ICAA - H01J-037/32 [2006-01 A - I R M EP]

ICCA - H01J-037/32 [2006 C - I R M EP]

UP - 2003-06

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PN - TW483021 B 20020411 [TW-483021]

AP - TW89125958 20001206 [2000TW-0125958]

ACT - 20020821 TW/GD4A-A [+]

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7/12 PLUSPAT - @QUESTEL-ORBIT - image

PN - The US6020592 A 20000201 [US6020592]

STG - (A) United States patent

TI - (A) Dose monitor for plasma doping system

PA - (A) VARIAN SEMICONDUCTOR EQUIPMENT (US)

PA0 - Varian Semiconductor Equipment Associates, Inc., Gloucester MA [US]

IN - (A) LIEBERT REUEL B (US); PEDERSEN BJORN O (US); GOECKNER MATTHEW

(US)

IC (A) H01J-037/244 AP US12837098 19980803 [1998US-0128370] PR US12837098 19980803 [1998US-0128370] ICAA -H01J-037/32 [2006-01 A - I R M EP] ICCA -H01J-037/32 [2006 C - I R M EP] EC H01J-037/32D1C1 H01J-037/32J ICO T01J-237/244A **PCL** ORIGINAL (O): 250492210 DT Basic I/I LEGALI - ©EPO PN US6020592 A 20000201 [US6020592] AP ÚS12837098 19980803 [1998US-0128370] ACT 20010619 US/RF-A REISSUE APPLICATION FILED **EFFECTIVE DATE: 20010417** UP 2003-22 8/12 PLUSPAT + @QUESTEL-ORBIT - image L US6300643 B1 20011009 [US6300643] PN STG (B1) U.S. Patent (no pre-grant pub.) after Jan. 2, 2001 (B1) Dose monitor for plasma doping system TI (B1) VARIAN SEMICONDUCTOR EQUIPMENT (US) PA Varian Semiconductor Equipment Associates, Inc., Gloucester MA [US] PA₀ IN (B1) FANG ZIWEI (US); GOECKNER MATTHEW (US) IC (B1) H01J-037/244 AP US45555099 19991206 [1999US-0455550] US45555099 19991206 [1999US-0455550] PR US12837098 19980803 [1998US-0128370] **ICAA** 'H01J-037/32 [2006-01 A - I R M EP] **ICCA** H01J-037/32 [2006 C - I R M EP] EC H01J-037/32D1C1 H01J-037/32J ICO · -T01J-237/244A ORIGINAL (O): 250492210; CROSS-REFERENCE (X): 250397000 PCL Corresponding document DT

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UP

2001-42

PN - US6300643 B1 20011009 [US6300643]

AP US45555099 19991206 [1999US-0455550] ACT 20000228 US/AS-A ASSIGNMENT OWNER: VARIAN SEMICONDUCTOR EQUIPMENT ASSOCIATES, INC. 35 ASSIGNMENT OF ASSIGNORS INTEREST: ASSIGNORS: FANG, ZIWEI: GOECKNER, MATTHEW; REEL/FRAME: 010583/0565; SIGNING DATES FROM 20000210 TO 20000212 20030429 US/CC-A CERTIFICATE OF CORRECTION UP 2004-26 À 9/12 PLUSPAT - @QUESTEL-ORBIT - image PN STG (A1) Utility Patent Application published on or after January 2, 2001 TI . (A1) Dose monitor for plasma doping system IN (A1) LIEBERT REUEL B (US); GOECKNER MATTHEW (US); PEDERSEN BJORN O · (US) IC (A1) G21K-005/10 H01J-037/08 AP US83688201 20010417 [2001US-0836882] PR US83688201 20010417 [2001US-0836882] US45555099 19991206 [1999US-0455550] US12837098 19980803 [1998US-0128370] H01J-037/32 [2006-01 A - I R M EP] ICAA -ICCA - ' H01J-037/32 [2006 C - I R M EP] EC H01J-037/32D1C1 H01J-037/32J T01J-237/244A ICO ORIGINAL (O): 250492210 PCL Corresponding document DT 2002-12 UP 10 / 12 PLUSPAT - @QUESTEL-ORBIT - image Talus 2001042827 A1 20011122 [US20010042827] PN (A1) Utility Patent Application published on or after January 2, 2001 **STG** TI (A1) Dose monitor for plasma doping system (A1) VARIAN SEMICONDUCTOR EQUIPMENT (US) PA Varian Semiconductor Equipment Associates, Inc., Gloucester MA [US] PA₀ (A1) FANG ZIWEI (US); GOECKNER MATTHEW (US) IN (A1) B01D-059/44 H01J-049/00 IC DUS6528805 B2 20030304 [US6528805] PN₂ STG2 (B2) U.S. Patent (with pre-grant pub.) after Jan. 2, 2001

TI2

(B2) Dose monitor for plasma doping system

PA2 - (B2) VARIAN SEMICONDUCTOR EQUIPMENT (US)

IN2 - (B2) FANG ZIWEI (US); GOECKNER MATTHEW (US)

IC2 - (B2) H01J-037/244

AP - US91699801 20010727 [2001US-0916998]

PR - US91699801 20010727 [2001US-0916998]

US45555099 19991206 [1999US-0455550] US12837098 19980803 [1998US-0128370]

ICAA - H01J-037/32 [2006-01 A - I R M EP]

ICCA - H01J-037/32 [2006 C - I R M EP]

EC - H01J-037/32D1C1

H01J-037/32J

ICO - T01J-237/244A

PCL - ORIGINAL (O): 250492210; CROSS-REFERENCE (X): 250397000

DT - Corresponding document

UP - 2001-48

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11/12 PLUSPAT - @QUESTEL-ORBIT - image

PN - **W**O200008670 A2 20000217 [WO200008670]

STG - (A2) Publ. Of int. Appl. W/out int. Search rep

TI - (A2) DOSE MONITOR FOR PLASMA-IMMERSION ION IMPLANTATION DOPING SYSTEM

OTI - (A2) CONTROLE DES DOSES POUR SYSTEME DE DOPAGE A IMPLANTATION D'IONS ET IMMERSION DANS DU PLASMA

PA - (A2) VARIAN SEMICONDUCTOR EQUIPMENT (US)

PA0 - VARIAN SEMICONDUCTOR EQUIPMENT ASSOCIATES, INC.; 35 Dory Road Gloucester, MA 01930 (US)

IN - (A2) LIEBERT REUEL B; PEDERSEN BJORN O; GOECKNER MATTHEW

IC - (A2) C23C-014/48 H01J-037/32

PN2 - WO200008670 A3 20000608 [WO200008670]

STG2 - (A3) Subsqu. Publ. Of int. Search report

TI2 - (A3) DOSE MONITOR FOR PLASMA-MONITOR ION IMPLANTATION DOPING SYSTEM

OTI2 - (A3) CONTROLE DES DOSES POUR SYSTEME DE DOPAGE A IMPLANTATION D'IONS ET IMMERSION DANS DU PLASMA

PA2 - (A3) VARIAN SEMICONDUCTOR EQUIPMENT (US)

IN2 - (A3) LIEBERT REUEL B; PEDERSEN BJORN O; GOECKNER MATTHEW

IC2 - (A3) C23C-014/48 H01J-037/32

PN3 - WO200008670 A9 20000727 [WO200008670]

STG3 - (A9) Complete corrected document

TI3 - (A9) DOSE MONITOR FOR PLASMA-MONITOR ION IMPLANTATION DOPING SYSTEM

OTI3 - (A9) CONTROLE DES DOSES POUR SYSTEME DE DOPAGE A IMPLANTATION D'IONS ET IMMERSION DANS DU PLASMA

PA3 - (A9) VARIAN SEMICONDUCTOR EQUIPMENT (US)

IN3 - (A9) LIEBERT REUEL B; PEDERSEN BJORN O; GOECKNER MATTHEW

IC3 - (A9) C23C-014/48 H01J-037/32

LA - ENGLISH (ENG)

AP - WOUS9915790 19990713 [1999WO-US15790]

PR - US12837098 19980803 [1998US-0128370]

ICAA - H01J-037/32 [2006-01 A - I R M EP]

ICCA - H01J-037/32 [2006 C - I R M EP]

EC - H01J-037/32D1C1

H01J-037/32J

ICO - T01J-237/244A

DS - JP; KR; European Patent (AT; BE; CH; CY; DE; DK; ES; FI; FR; GB; GR; IE; IT; LU; MC;

NL; PT; SE)

DT - Corresponding document

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PN - WO200008670 A2 20000217 [WO200008670]WO200008670 A3 20000608

[WO200008670]WO200008670 A9 20000727 [WO200008670]

AP - WOUS9915790 19990713 [1999WO-US15790]

ACT - 20000217 WO/AK [+]

DESIGNATED STATES CITED IN A SUBSEQUENTLY PUBLISHED SEARCH REPORT

20000217 WO/AL [+]

DESIGNATED COUNTRIES FOR REGIONAL PATENTS CITED IN A

SUBSEQUENTLY PUBLISHED SEARCH REPORT

AT BE CH CY DE DK ES FI FR GB GR IE IT LU MC NL PT SE

20000406 WO/DFPE

REQUEST FOR PRELIMINARY EXAMINATION FILED PRIOR TO EXPIRATION OF 19TH MONTH FROM PRIORITY DATE

20000412 WO/121

EP: THE EPO HAS BEEN INFORMED BY WIPO THAT EP WAS DESIGNATED IN THIS APPLICATION

20000608 WO/AK [+]

DESIGNATED STATES CITED IN A SUBSEQUENTLY PUBLISHED SEARCH REPORT
JP KR

20000608 WO/AL [+]

DESIGNATED COUNTRIES FOR REGIONAL PATENTS CITED IN A

SUBSEQUENTLY PUBLISHED SEARCH REPORT

AT BE CH CY DE DK ES FI FR GB GR IE IT LU MC NL PT SE

20000727 WO/AK [+]

DESIGNATED STATES CITED IN A SUBSEQUENTLY PUBLISHED SEARCH REPORT

JP KR

20000727 WO/AL [+]

DESIGNATED COUNTRIES FOR REGIONAL PATENTS CITED IN A

SUBSEQUENTLY PUBLISHED SEARCH REPORT

AT BE CH CY DE DK ES FI FR GB GR IE IT LU MC NL PT SE

UP - 2003-22

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12 / 12 PLUSPAT - @QUESTEL-ORBIT - image

PN - WO200141183 A1 20010607 [WO200141183]

STG - (A1) Publ. Of int. Appl. With int. Search rep

TI - (A1) DOSE MONITOR FOR PLASMA DOPING SYSTEM

OTI - (A1) CONTROLE DES DOSES POUR SYSTEME DE DOPAGE AU PLASMA

PA - (A1) VARIAN SEMICONDUCTOR EQUIPMENT (US)

PAO - VARIAN SEMICONDUCTOR EQUIPMENT ASSOCIATES, INC.; 35 Dory Road, Gloucester, MA 01930 (US)

(A1) FANG ZIWEI (US); GOECKNER MATTHEW (US)

IC - (A1) H01J-037/244 H01J-037/32

PN2 - WO200141183 A8 20020523 [WO200141183]

STG2 - (A8) Modified first page

TI2 - (A8) DOSE MONITOR FOR PLASMA DOPING SYSTEM

OTI2 - (A8) CONTROLE DES DOSES POUR SYSTEME DE DOPAGE AU PLASMA

PA2 - (A8) VARIAN SEMICONDUCTOR EQUIPMENT (US)

IN2 - (A8) FANG ZIWEI (US); GOECKNER MATTHEW (US)

IC2 - (A8) H01J-037/244 H01J-037/32

PN3 - WO200141183 A9 20020620 [WO200141183]

STG3 - (A9) Complete corrected document

TI3 - (A9) DOSE MONITOR FOR PLASMA DOPING SYSTEM

OTI3 - (A9) CONTROLE DES DOSES POUR SYSTEME DE DOPAGE AU PLASMA

PA3 - (A9) VARIAN SEMICONDUCTOR EQUIPMENT (US)

IN3 - (A'9) FANG ZIWEI (US); GOECKNER MATTHEW (US)

IC3 - (A9) H01J-037/244 H01J-037/32

LA - ENGLISH (ENG)

AP - WOUS0032576 20001129 [2000WO-US32576]

PR - US45555099 19991206 [1999US-0455550]

ICAA - H01J-037/32 [2006-01 A - I R M EP]

ICCA - H01J-037/32 [2006 C - I R M EP]

EC - H01J-037/32D1C1

H01J-037/32J

DS - IL; JP; KR; European Patent (AT; BE; CH; CY; DE; DK; ES; FI; FR; GB; GR; IE; IT; LU;

MC; NL; PT; SE; TR)

DT - Basic

UP - 2001-24

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PN - WO

WO200141183 A1 20010607 [WO200141183]WO200141183 A8 20020523

[WO200141183]WO200141183 A9 20020620 [WO200141183]

AP -

WOUS0032576 20001129 [2000WO-US32576]

ACT

20010607 WO/AK [+] DESIGNATED STATES

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20010607 WO/AL [+]

DESIGNATED COUNTRIES FOR REGIONAL PATENTS

AT BE CH CY DE DK ES FI FR GB GR IE IT LU MC NL PT SE TR

20010801 WO/121

EP: THE EPO HAS BEEN INFORMED BY WIPO THAT EP WAS DESIGNATED IN

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DESIGNATED COUNTRIES FOR REGIONAL PATENTS

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20020531 WO/ENP

ENTRY INTO THE NATIONAL PHASE IN:

JP 2001 542358A [2001JP-0542358]

20020605 WO/WWE [+]

WIPO INFORMATION: ENTRY INTO NATIONAL PHASE

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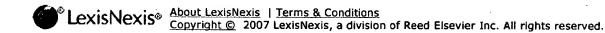
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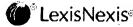
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